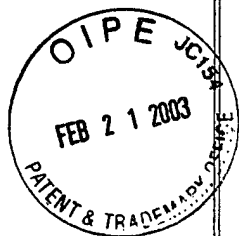


2823



PATENT  
Customer No. 22,852  
Attorney Docket No. 08244.0026

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Sun-oo KIM

Application No.: 09/739,743

Filed: December 20, 2000

For: METHOD FOR  
MANUFACTURING INTERLAYER  
DIELECTRIC LAYER IN A  
SEMICONDUCTOR DEVICE

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) Group Art Unit: 2823  
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) Examiner: W. Coleman  
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TECHNOLOGY CENTER 2800

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action of November 21, 2002, please amend the application  
as follows:

IN THE CLAIMS:

Please cancel claim 1 without prejudice or disclaimer of the subject matter  
thereof, rewrite claim 2 in independent form, and amend claims 3-5, and 7, as follows:

2. (Amended) A method for manufacturing an interlayer dielectric layer, the  
method comprising the steps of:

a) setting an active matrix provided with a substrate and interconnections formed  
on the substrate in a chamber;

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